

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of :  
Huang, et al.

Group Art Unit: 1752

Serial No.: 10/537,259

Examiner: Geraldine Letscher

Filed: 05/31/2005

Confirmation No.: 1422

TITLE: High Sensitivity Resist Compositions  
For Electron-Based Lithography

Date: 08/24/2006

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to the duty of disclosure set forth in 37 C.F.R. § 1.56, and further pursuant to the provisions of 37 C.F.R. §§ 1.97 and 1.98, applicants hereby respectfully submit Abstracts of the Foreign Patents as listed on Form PTO-1449, attached hereto.

Each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

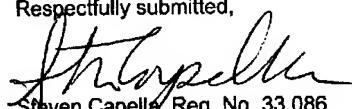
In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable. No fee is believed to be due for this submission. If any fees are required, however, the Commissioner is hereby authorized to charge such fees to Deposit Account No. 09-0458.

CONCLUSION

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants' undersigned agent may be reached by telephone at (845)894-3669. All correspondence should continue to be directed to the address listed below.

Respectfully submitted,



Steven Capella, Reg. No. 33,086  
Attorney for Applicant.

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Hopewell Junction, NY 12533

FIS920020051US1

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <b>FIS920020051US1</b>		Application Number <b>10/537,259</b>	
				Applicant(s) <b>Huang, et al.</b>			
				Filing Date <b>05/31/2005</b>		Group Art Unit <b>1752</b>	
				<b>U.S. PATENT DOCUMENTS</b>			

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

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<b>FOREIGN PATENT DOCUMENTS</b>							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
							YES
		PUPA 09-323970	1997-12-16	JP			✓
		PUPA 08-248626	1996-09-27	JP			✓
		PUPA 10-007650	1998-01-13	JP			✓
		PUPA 09-160244	1997-06-20	JP			✓
		PUPA 06-043653	1994-02-18	JP			✓

<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							

EXAMINER				DATE CONSIDERED			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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				Applicant(s) <b>Huang, et al.</b>			
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<b>U.S. PATENT APPLICATION PUBLICATIONS</b>							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<b>FOREIGN PATENT DOCUMENTS</b>							
REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	PUPA 2001-209181	2001-08-03	JP			✓	
	PUPA 09-222724	1997-08-26	JP			✓	
	PUPA 2000-019732	2000-01-21	JP			✓	
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
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